



**PATENT NUMBER**

**U.S. UTILITY Patent Application**

O.I.P.E.

**PATENT DATE**

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SCANNED

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APPLICATION NO.	CONT/PRIOR	CLASS	SUBCLASS	ART UNIT	EXAMINER
09/618550	D-F	355	55	2851	H. Nguyen

NTS Tetsuo Taniguchi  
2010

1. Exposure method and lithography system, exposure apparatus and method of making the apparatus, and method of manufacturing device

PTO-2040  
12/99

## ISSUING CLASSIFICATION

Continued on Issue Slip Inside File Jacket

TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.				NOTICE OF ALLOWANCE MAILED	
	(Assistant Examiner) _____ (Date)				
<input checked="" type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____				ISSUE FEE	
	(Primary Examiner) _____ (Date)			Amount Due	Date Paid
<input type="checkbox"/> The terminal _____ months of this patent have been disclaimed.				ISSUE BATCH NUMBER	
	(Legal Instruments Examiner) _____ (Date)				

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